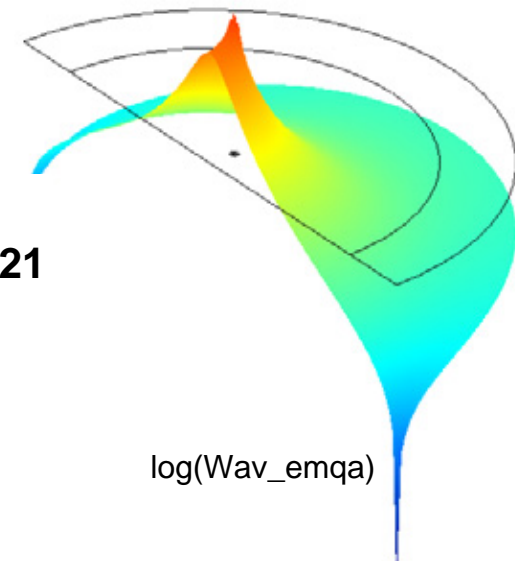
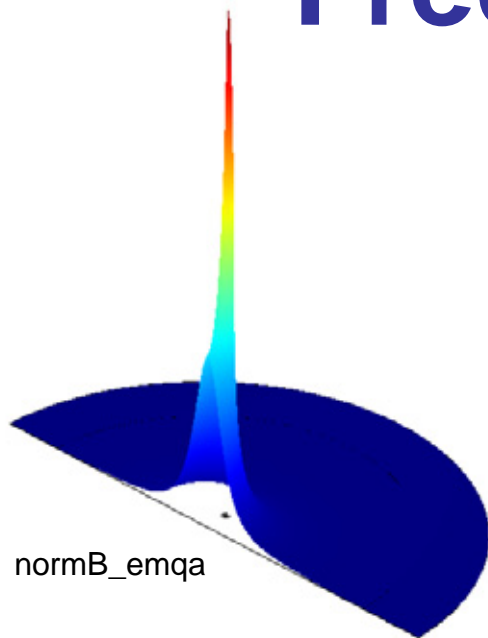


Inductance of Magnetic Plated Wires as a Function of Frequency and Plating Thickness

Thomas Graf and Othmar Schälli
Hochschule Luzern, Technikumstrasse 21
CH-6048 Horw, Switzerland



Motivation

減させることができます。これは磁性シールド層により、コイルに生じる近接効果の影響を軽減し、導体の電流分布を均一にし、導体の実効抵抗を低減しうるためです。

Magnet-plated Wire (magnetic wire) is a copper conductor covered with a thin layer of highly magnetic material, over which a polyurethane insulating film is enameled. When used for high-frequency coils, it reduces high-frequency losses by 10% compared to conventional polyurethane enameled copper wire. The reduction is due to the magnetic shielding, which lowers the proximity effect generally occurring in these types of coil, evenly distributes electric current in the conductor, and decreases the effective resistance of the conductor.

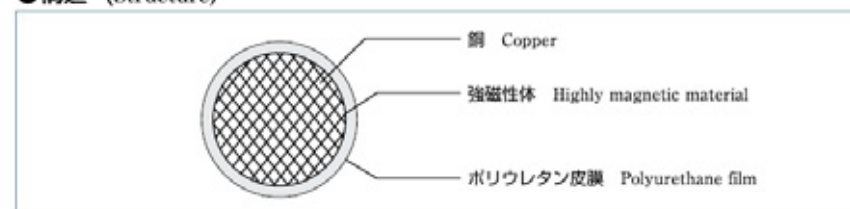
●特長 Features

- 高周波コイルのQ特性が向上します。●はんだ付けが可能です。
- 部品が小型化できます。●高性能なコイルの設計が可能です。
- Q-characteristics of high-frequency coils are improved. ●The wire is solderable.
- Components can be miniaturized. ●High-performance coils can be designed.

- Applications : High frequency coils, delay lines.
- 製造範囲 (Range of manufacture) 絶縁皮膜のUEのみ

記号 Code	最高使用周波数帯 (MHz) Maximum Frequency Band Used (MHz)	絶縁皮膜 Insulating Film	製造範囲 (mm) Range of Manufacture
UEFPW	4.5	UE	0.05~0.12
	10.7		

●構造 (Structure)



- Applications : High frequency coils, delay lines.
- 製造範囲 (Range of manufacture) 絶縁皮膜のUEのみ

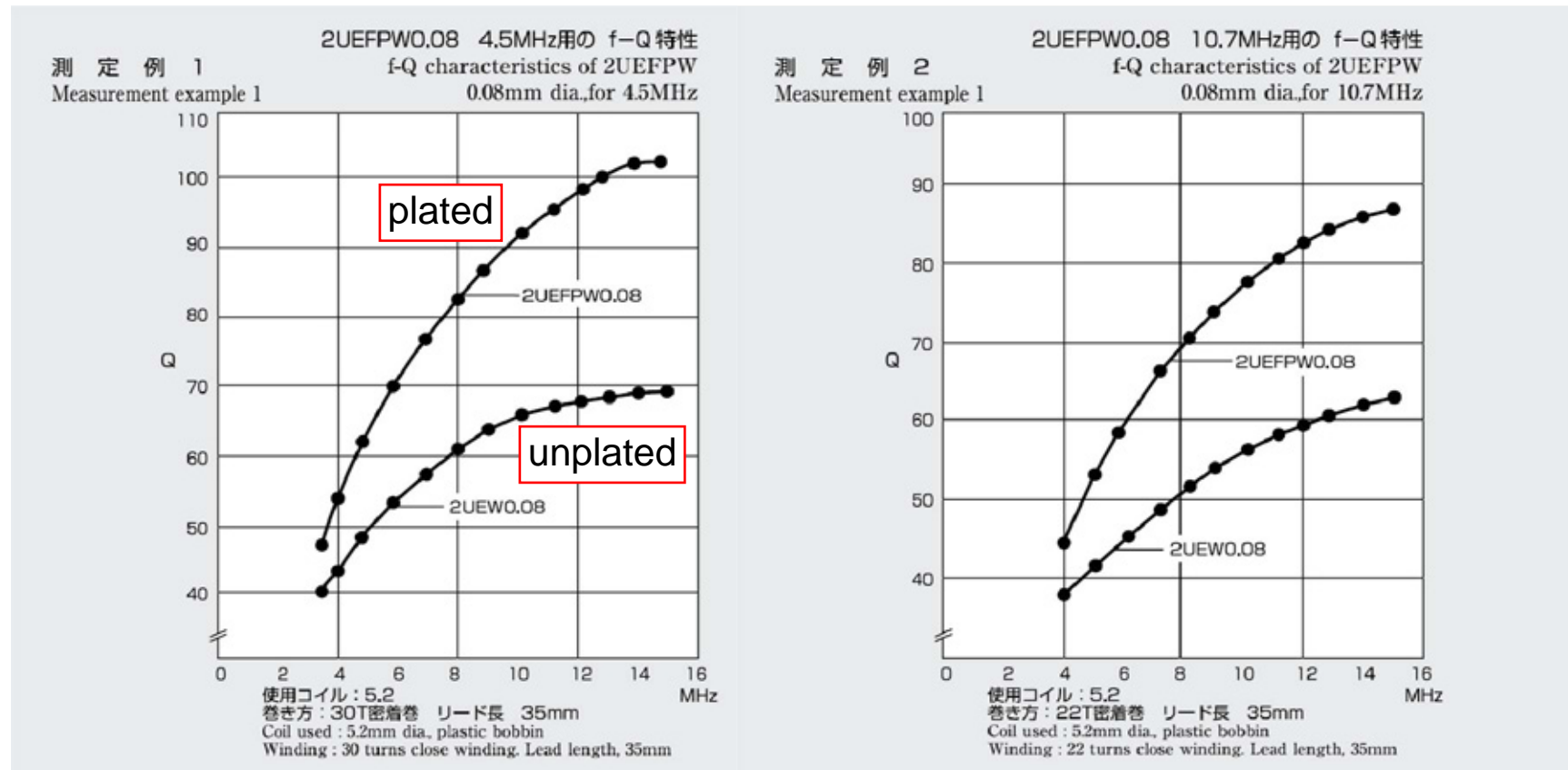
記号 Code	最高使用周波数帯 (MHz) Maximum Frequency Band Used (MHz)	絶縁皮膜 Insulating Film	製造範囲 (mm) Range of Manufacture
UEFPW	4.5	UE	0.05~0.12
	10.7		

Improved Q-characteristics of high-frequency coils

Motivation

Magnet-plated Wire (magnetic wire) is a copper conductor covered with a thin layer of highly magnetic material, over which a polyurethane insulating film is enameled. When used for high-frequency coils, it reduces high-frequency losses by 10% compared to conventional polyurethane enameled copper wire. The reduction is due to the magnetic shielding, which lowers the proximity effect generally occurring in these types of coil, evenly distributes electric current in the conductor, and decreases the effective resistance of the conductor.

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Outline

- Equations for Resistance R, Inductance L and Skin Depth δ_{Skin}

- Single Loop Analysis for a Microscopic Understanding
 - COMSOL Simulation
 - Results and Discussion
 - Scaling

- Coil Analysis and Comparison with Experiment
 - COMSOL Simulation
 - Results and Validation with Experiment

- Summary

Equations

COMSOL

resistance **R**:

$$R = \text{real} \left(\frac{V_{\text{Loop}}}{I} \right)$$

R via geometry and σ

$$R = \frac{1}{\sigma} \cdot \frac{L}{A_{\text{eff}}} \approx \frac{1}{\sigma} \cdot \frac{D\pi}{d\pi \cdot d_{\text{eff}}}$$

loop circumference L
 effective current cross-sectional area A_{eff}
 D
 d
 d_{eff}

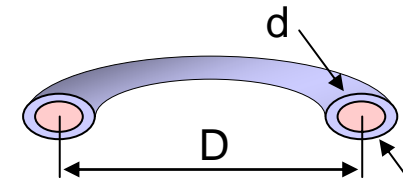
inductance **L**:

$$L_e = \text{imag} \left(\frac{V_{\text{Loop}}}{I \cdot 2\pi f} \right)$$

via electric potential

$$L_m = 2 \cdot \frac{E_{\text{mag. field}}}{I^2}$$

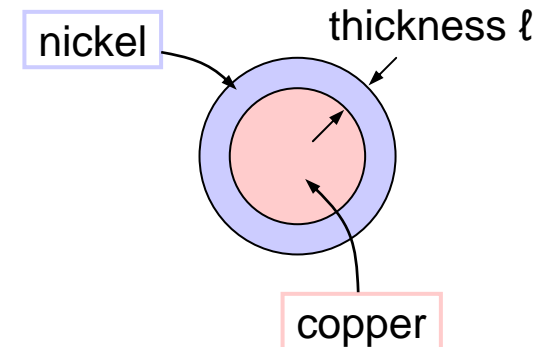
via magnetic field energy



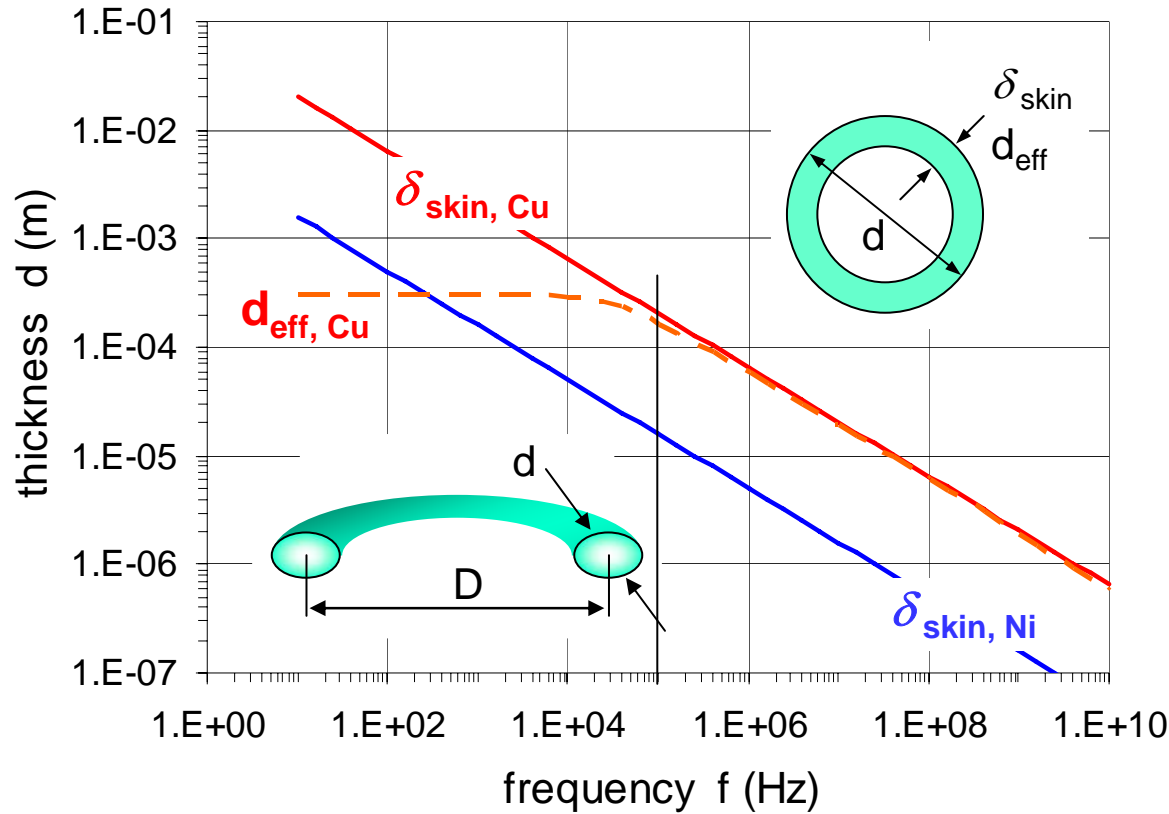
quality factor **Q**:

$$Q = \frac{2\pi f \cdot L}{R}$$

L_e
 L_m



Current Layer d , δ vs. f



Analytic expression for skin depth (J.D Jackson, Classical ED):

$$\delta_{\text{skin}} = \sqrt{\frac{1}{\mu_0 \cdot \mu_r \cdot \pi f \cdot \sigma}}$$

$$\mu_0 = 4\pi \times 10^{-7} \text{ T}\cdot\text{m/A}$$

μ_r = relative permeability

$\omega = 2\pi \times \text{frequency [1/s]}$

σ = conductivity [S/m]

Effective layer thickness d_{eff} :

$$d_{\text{eff}} = \frac{1}{\sigma \cdot R} \frac{D}{d} \cong \delta_{\text{skin}}$$

COMSOL

material and geometry

at high frequency

Behavior at High f

resistance **R**:

$$R_{\text{eff}} = \frac{1}{\sigma} \cdot \frac{L}{A_{\text{eff}}} \approx \frac{1}{\sigma} \cdot \frac{D\pi}{d\pi \cdot \delta_{\text{skin}}} = \frac{D}{d} \sqrt{\frac{\mu_0 \cdot \mu_r \cdot \pi}{\sigma}} \cdot \sqrt{f}$$

$$R_{\text{inf}} (f \rightarrow \infty) \sim f^{1/2}$$

inductance **L**:

$$L_e = \text{imag} \left(\frac{V_{\text{Loop}}}{I \cdot 2\pi f} \right) \sim \frac{V_{\text{Loop}}}{I \cdot f} \sim \frac{R}{f} = \frac{1}{\sqrt{f}}$$

"**inner**" inductance, via electric potential:
depends on skin depth

$$L_e (\delta_{\text{skin}} \leq l_{\text{plating}}) \sim f^{-1/2}$$

$$L_m = 2 \cdot \frac{E_{\text{mag. field}}}{I^2} \sim \frac{B^2}{I^2} \sim \frac{\mu^2}{I^2} = \text{const.}$$

"**outer**" inductance, via magnetic field energy:
depends on geometry only

$$L_{m,\text{inf}} (f \rightarrow \infty) \sim \text{const.}$$

$$L [\text{nH}] \approx 2 \frac{D\pi}{[\text{cm}]} \left(\ln \left(\frac{D\pi}{d} \right) - 1.07 \right)$$

($D > 20d$; Meinke, Springer, 1992)

$$Q_e (\delta_{\text{skin}} \leq l_{\text{plating}}) \sim \text{const.}$$

quality factor **Q**:

$$Q = \frac{2\pi f \cdot L}{R}$$

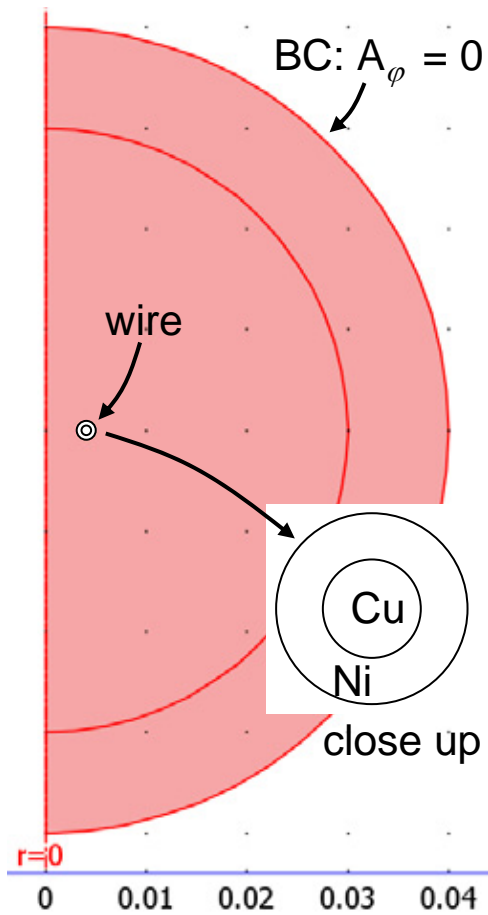
$$Q_e = \frac{2\pi f \cdot L_e}{R} \sim \frac{f \cdot f^{-1/2}}{\sqrt{f}}$$

$$Q_m = \frac{2\pi f \cdot L_m}{R} \sim \frac{f \cdot \text{const.}}{\sqrt{f}}$$

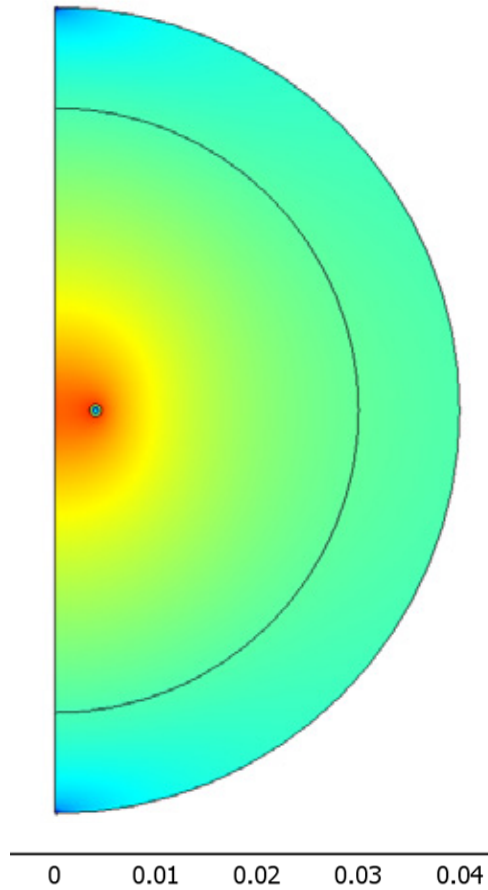
$$Q_{m,\text{inf}} (f \rightarrow \infty) \sim f^{1/2}$$

Cu-Ni Wire Loop

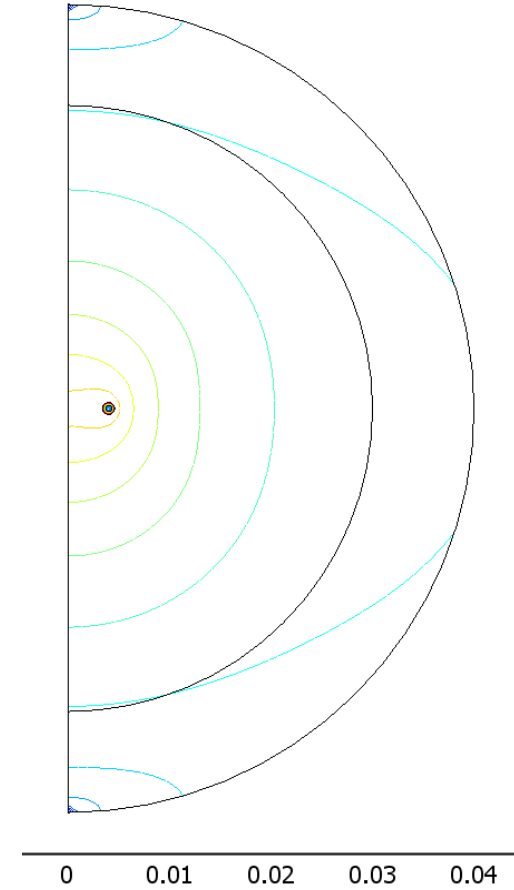
subdomains



Magnetic energy density
 $\log(W_{\text{mav_emqa}}), 10^5 \text{ Hz}$



Magnetic flux density
 $\log(\text{normB_emqa}), 10^5 \text{ Hz}$



Cu-Ni Wire Loop

Global Expressions

Name	Expression
R	real(Vin/(I3+I4))
Rp	R3*R4/(R3+R4)
Lm	2*2*Wm/abs(I3+I4)^2
Le	imag(Vin/(I3+I4))/(Omega)
Q	Omega*Le/R
Omega	2*pi*freq
Wm	WMag1+WMag2+WMag3+WMag4
Wm1	WMag1
Wm2	WMag2
Wm12	WMag1+WMag2
Wm3	WMag3
Wm4	WMag4
Wm34	WMag3+WMag4
R3	real(Vin/I3)
R4	real(Vin/I4)
dEff	D/d*1/(sigma3*R)

Subdomain Integration Variables

Name	Expression	Integration order
WMag1		
WMag2		
WMag3	2*pi*r*Wmav_emqa	4
I3	Jphi_emqa	4
I4		
WMag4		

Constants

Name	Expression	Value
Vin	1	1
sigma3	1.0e7[S/m]	1e7[S/m]
sigma4	6.0e7[S/m]	6e7[S/m]
D	0.008	0.008
d	0.0012	0.0012
mur3	1000	1000
mur4	1	1

Subdomain Settings - Azimuthal Induction Currents, Vector Potential (emqa)

Equation

$$(j\omega\sigma - \omega^2\epsilon_0\epsilon_r)\mathbf{A} + \nabla \times (\mu_0^{-1}\mu_r^{-1}\nabla \times \mathbf{A}) - \sigma\nabla \times (\nabla \times \mathbf{A}) = (\sigma V_{loop}/2nr + J_{\phi}^e)\mathbf{e}_{\phi}, \mathbf{A} = A_{\phi}\mathbf{e}_{\phi}$$

Subdomains: 1, 2, 3, 4

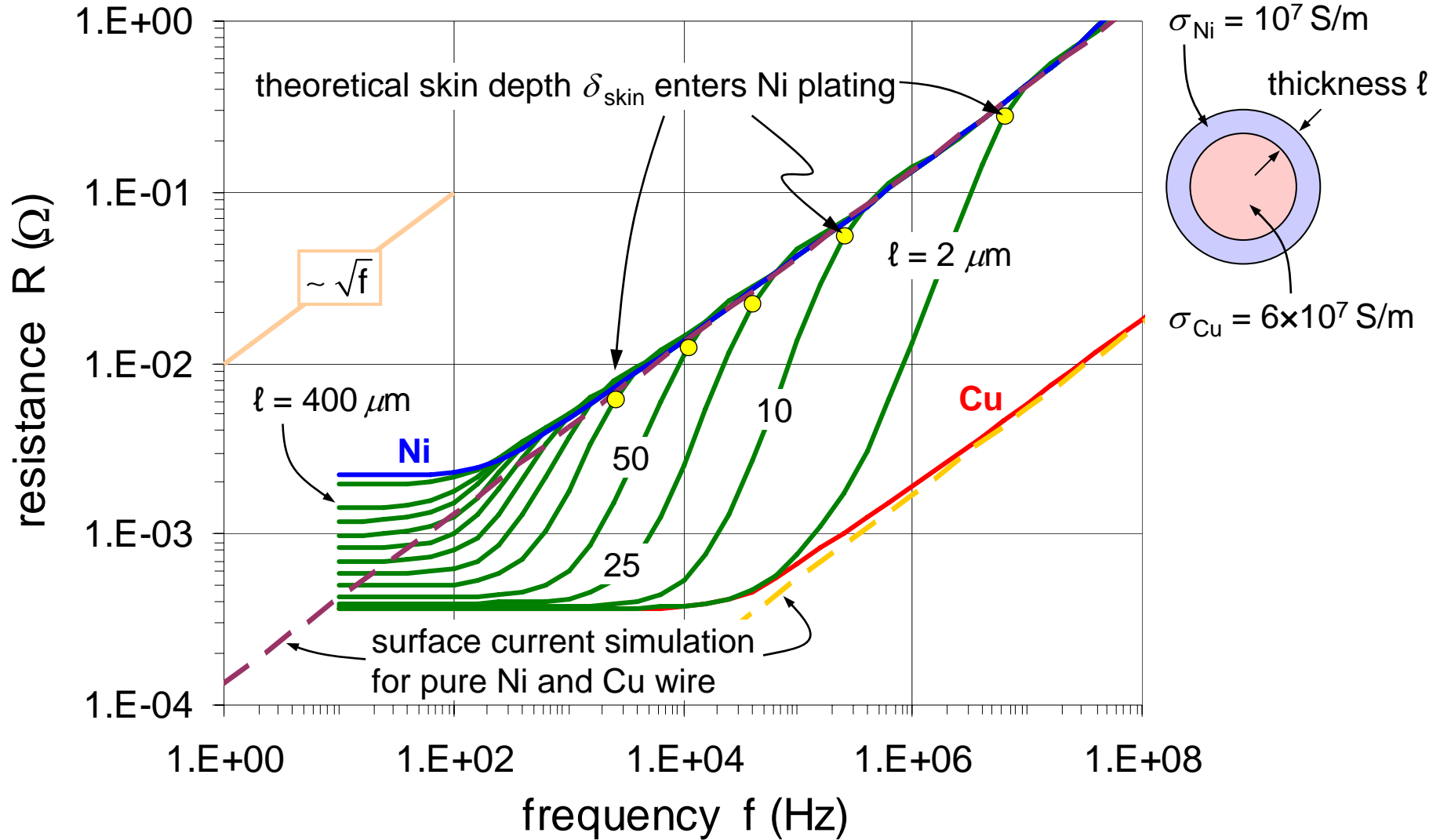
Electric material properties and current sources

Library material: Load...

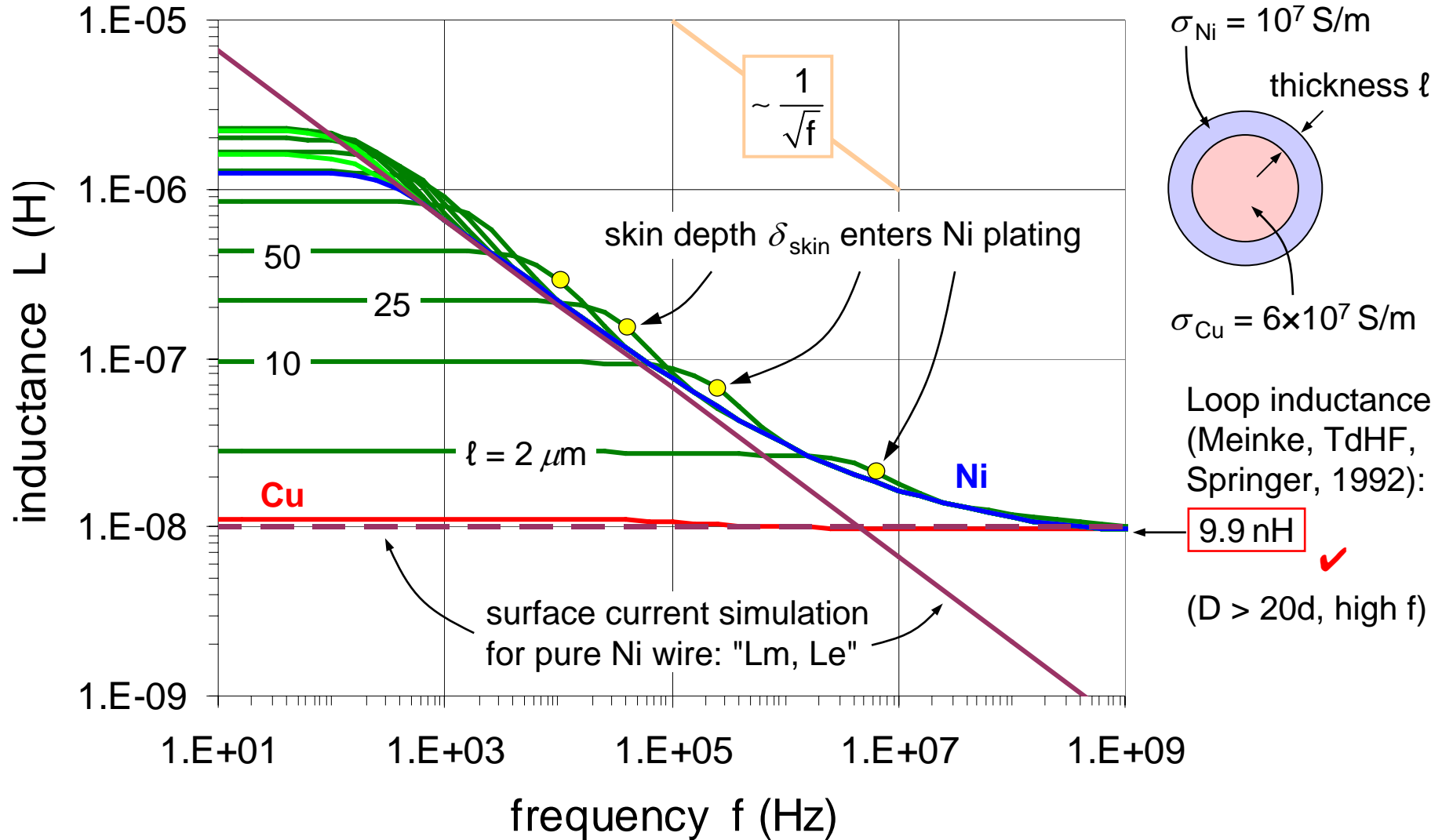
Constitutive relation: $\mathbf{D} = \epsilon_0\epsilon_r\mathbf{E}$ $\mathbf{D} = \epsilon_0\mathbf{E} + \mathbf{P}$ $\mathbf{D} = \epsilon_0\epsilon_r\mathbf{E} + \mathbf{D}_r$

Quantity	Value/Expression	Unit	Description
V_{loop}	Vin	V	Loop potential
J_{ϕ}^e	0	A/m ²	External current density
σ	sigma3	S/m	Electric conductivity
ϵ_r	1		Relative permittivity

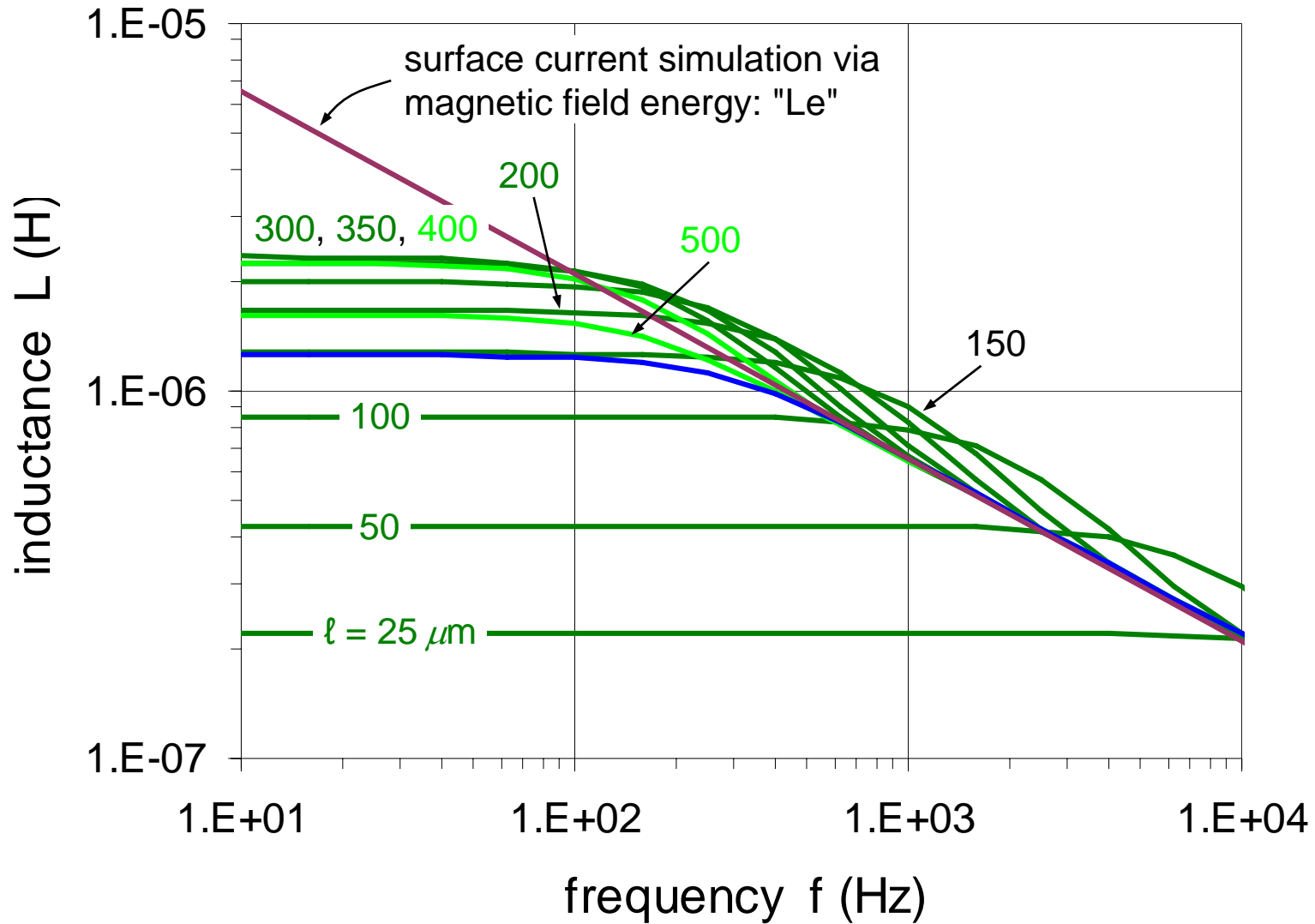
R versus f and ℓ



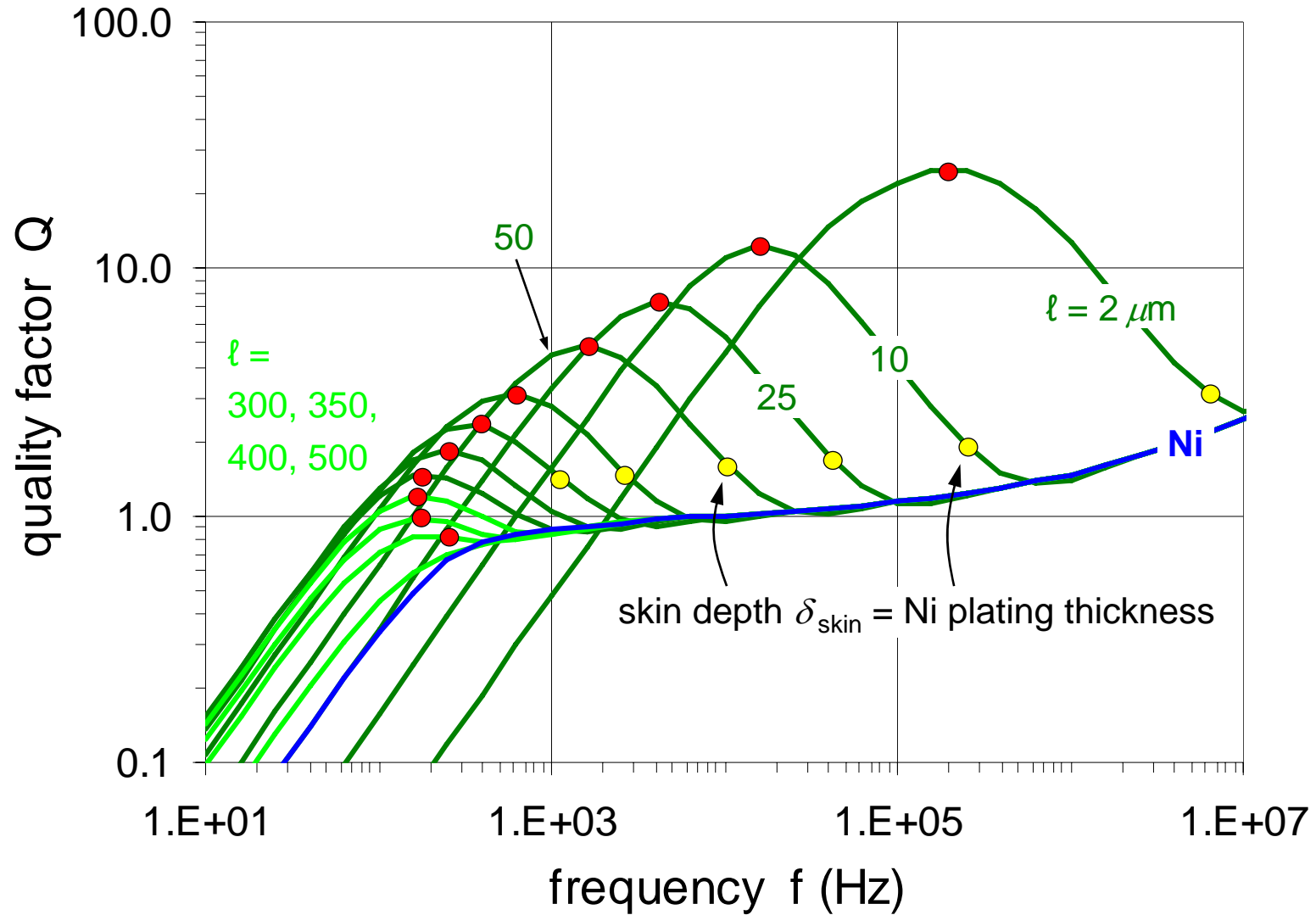
L versus f and ℓ



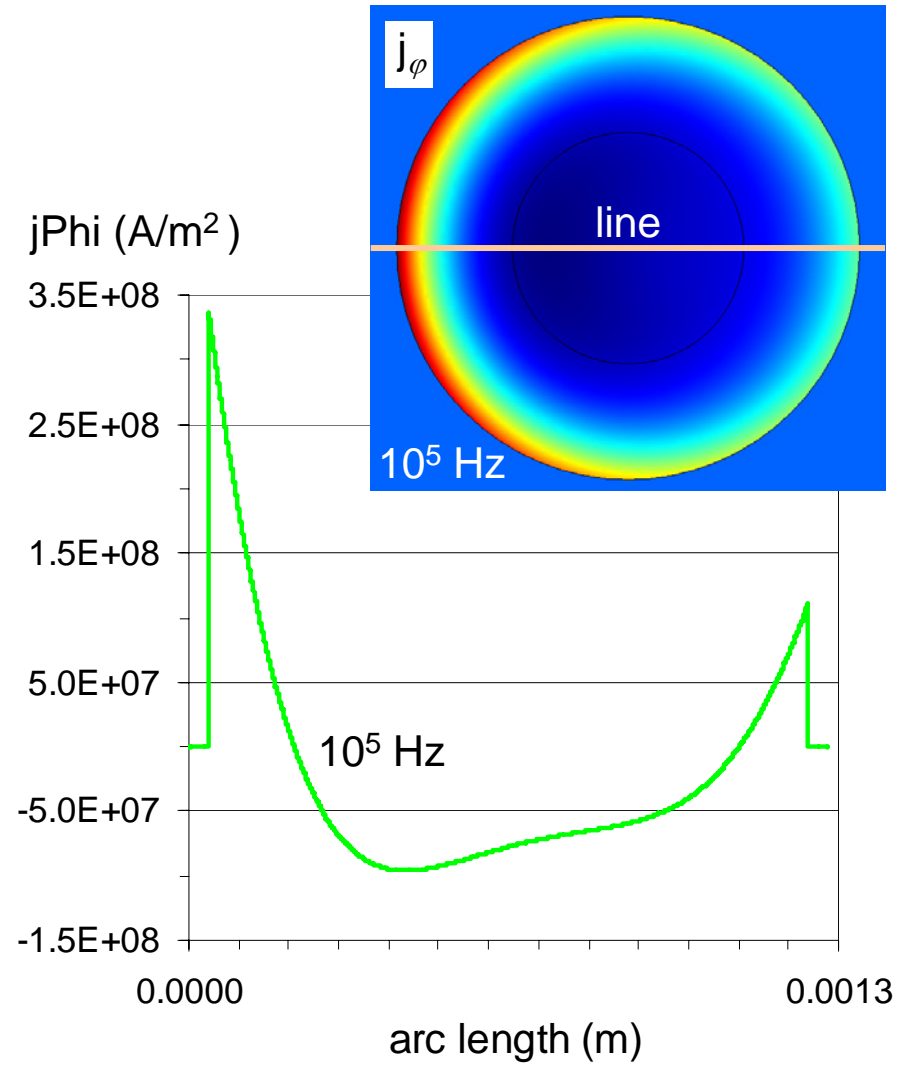
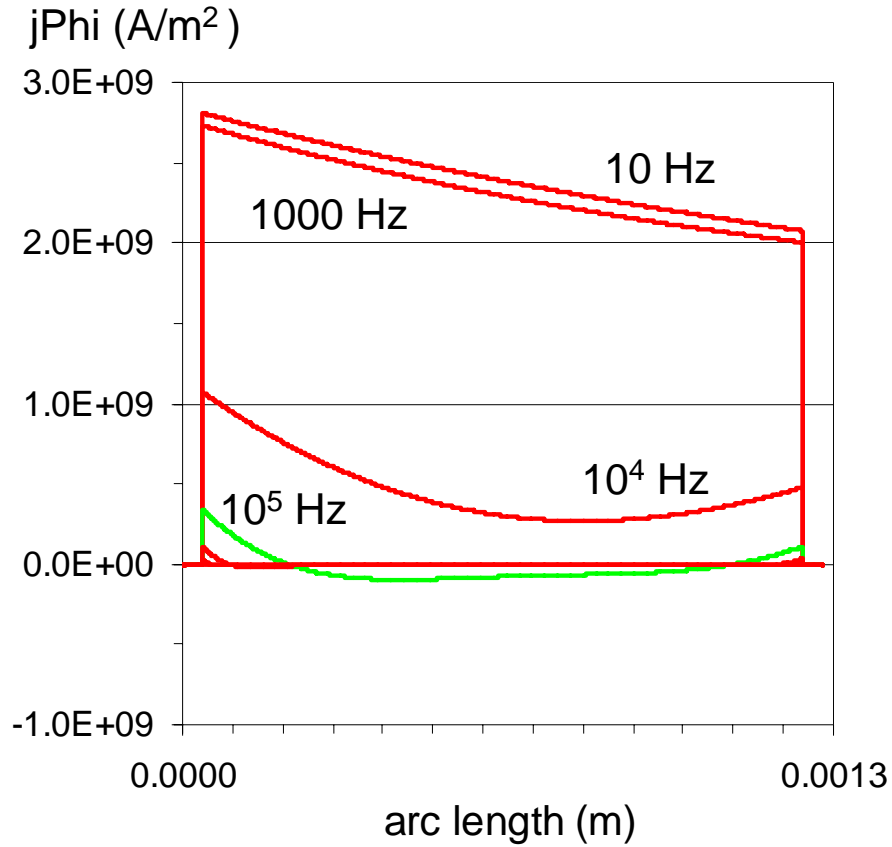
L versus f and ℓ , Inset



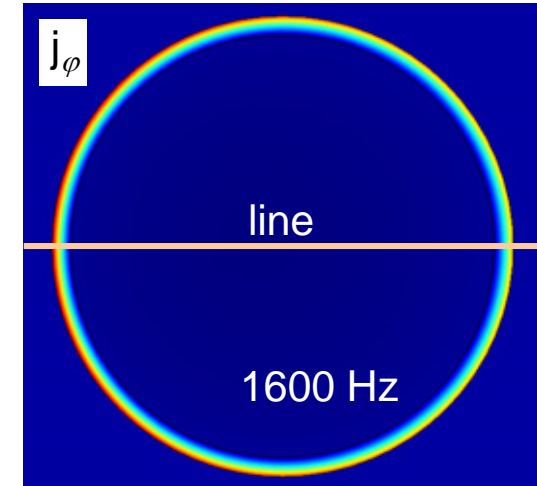
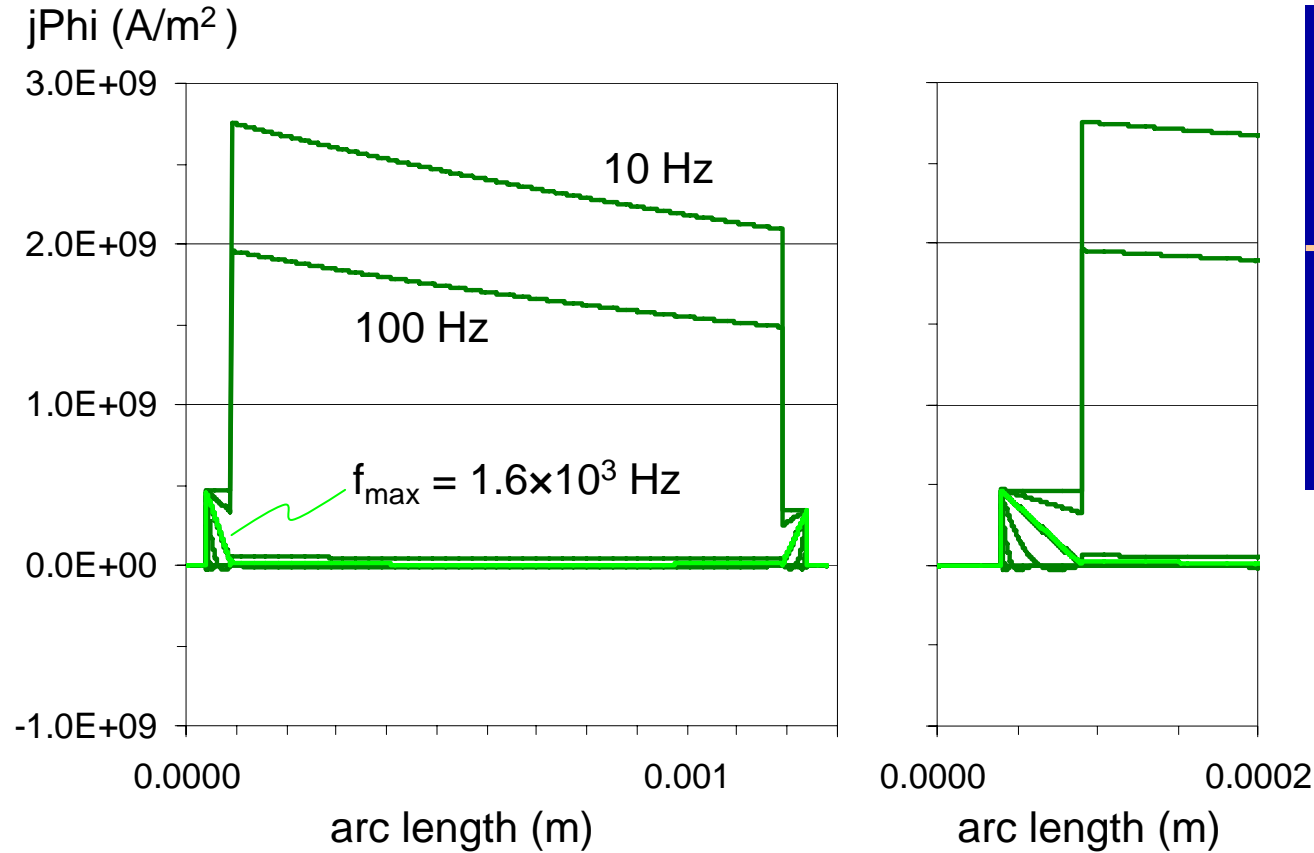
Q versus f and ℓ , Inset



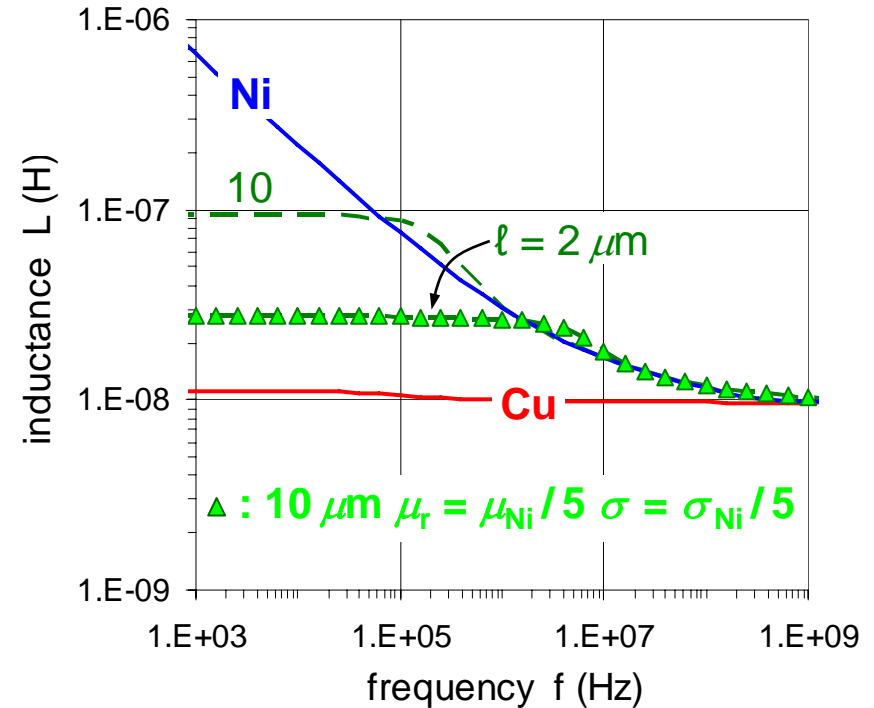
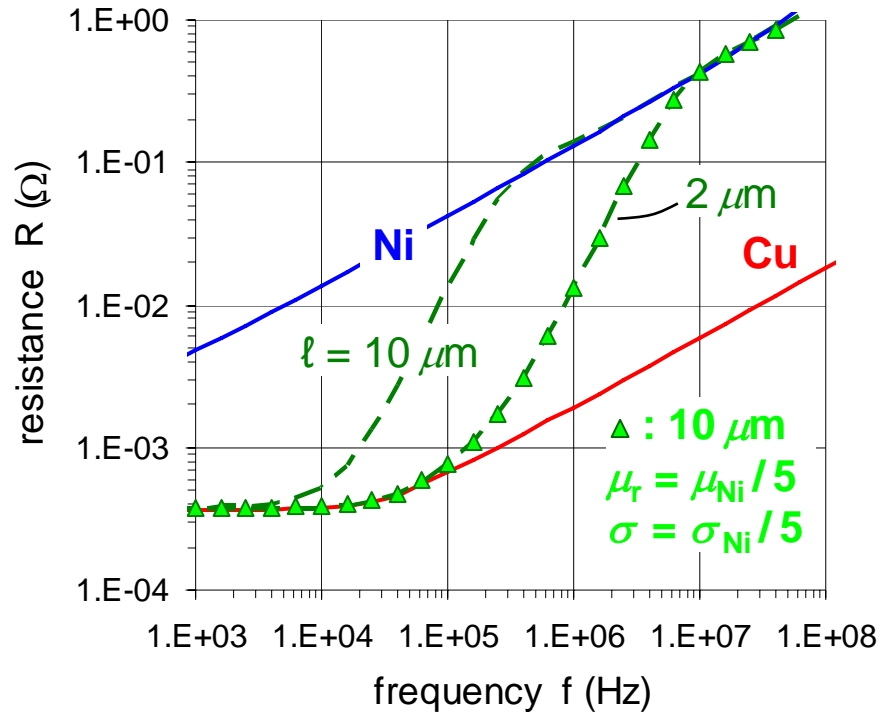
Cu-Loop, Line Plot: j_{Φ}



Ni(50 μ m)-Cu Loop, jPhi



Skaling



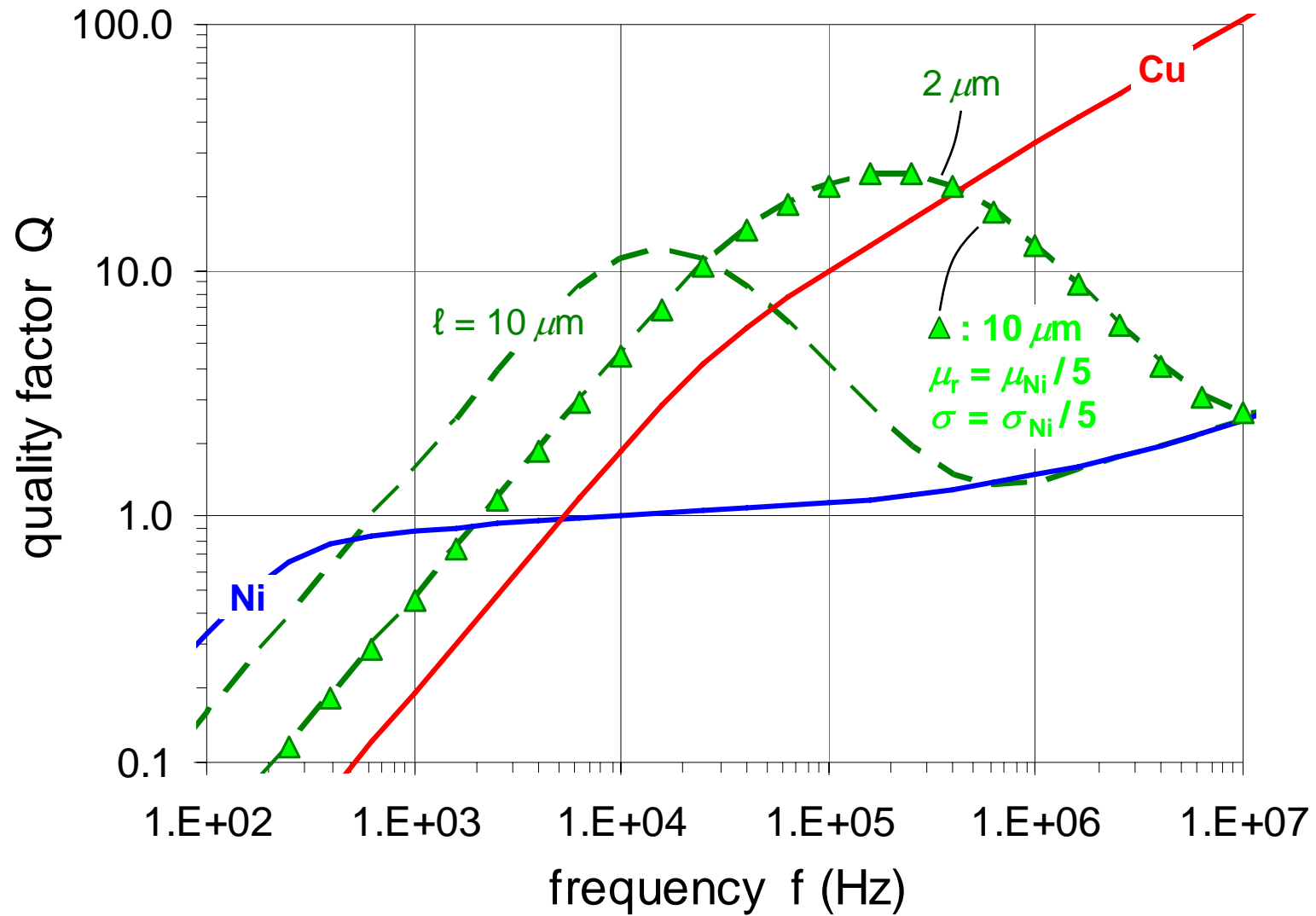
Same results, different plating thickness - Skaling for easier meshing! Example: $d_{\text{new}} = 5 \times d_{\text{old}}$

Increase δ_{skin} while keeping $R = \text{constant}$

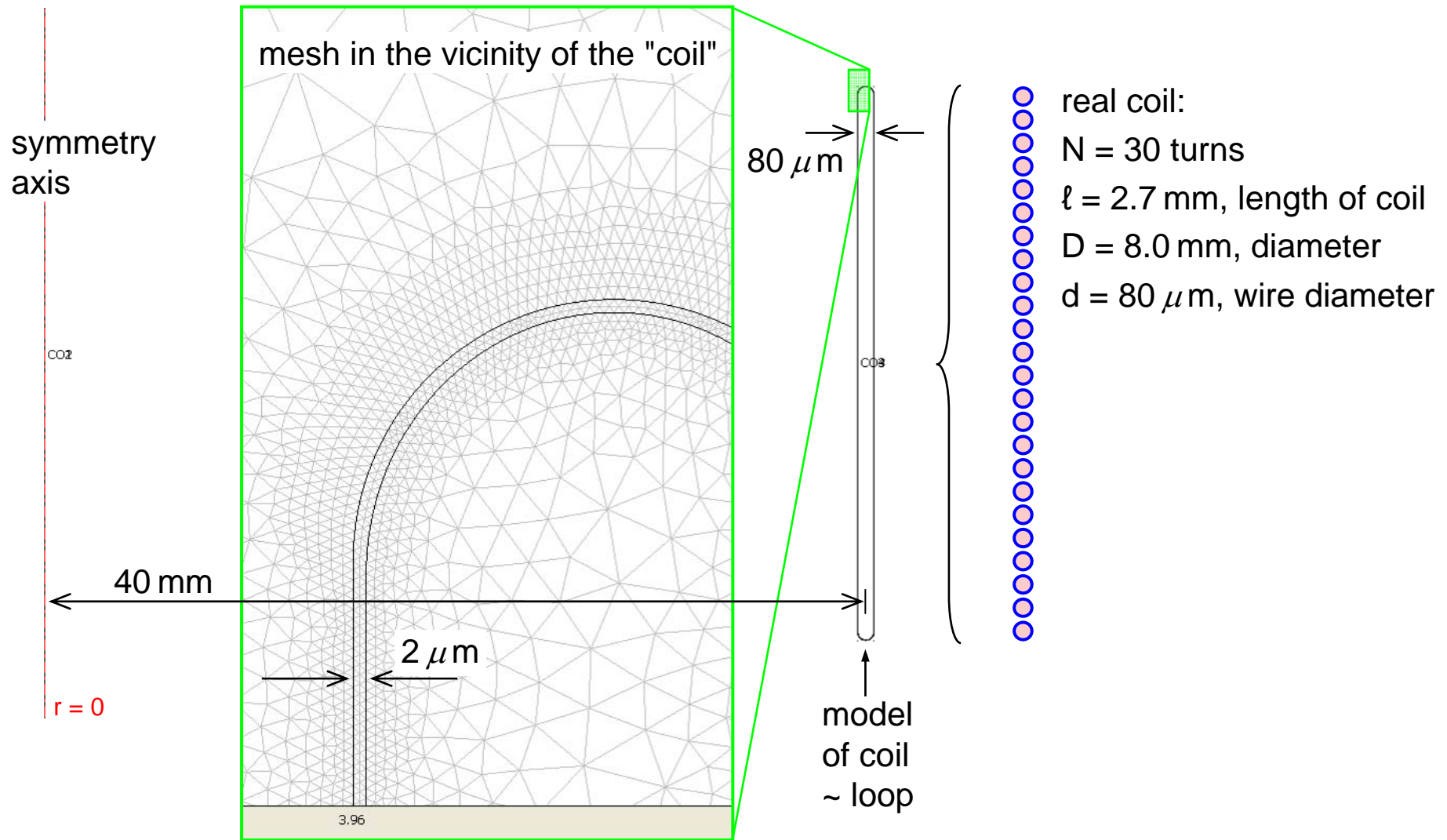
$$\delta_{\text{skin,new}} \equiv 5 \times \delta_{\text{skin,old}} = \sqrt{\frac{1}{\mu_0 \cdot \mu_r \cdot \pi f \cdot \sigma}}$$

$$R_{\text{new}} \equiv R_{\text{old}} = \frac{D}{d} \cdot \frac{1}{\sigma \cdot d}$$

Skaling



Plated Coil



Plated Coil

Name	Expression
R	real(Vin/(I3+I4))*turns^2
Rp	R3*R4/(R3+R4)
Lm	2*2*Wm/abs(I3+I4)^2*turns^2
Le	imag(Vin/(I3+I4))/(Omega)*turns^2
Q	Omega*Le/R
Omega	2*pi*freq
Wm	WMag1+WMag2+WMag3+WMag4
Wm1	WMag1
Wm2	WMag2
Wm12	WMag1+WMag2
Wm3	WMag3
Wm4	WMag4
Wm34	WMag3+WMag4
R3	real(Vin/I3)
R4	real(Vin/I4)

Source	Destination	Name	Expression
1		WMag1	
2		WMag2	
3		WMag3	2*pi*r*Wmag_emqa
4		I3	Jphi_emqa
		I4	
		WMag4	

$$R = \text{real} \left(\frac{V_{\text{Loop}} \cdot N}{I_{\text{Loop}} / N} \right) = \text{real} \left(\frac{V_{\text{Loop}}}{I_{\text{Loop}}} \right) \cdot N^2$$

$$L_e = \text{imag} \left(\frac{V_{\text{Loop}}}{I_{\text{Loop}} \cdot 2\pi f} \right) \cdot N^2$$

Subdomain Settings - Azimuthal Induction Currents, Vector Potential (emqa)

Equation

$$(j\omega\sigma - \omega^2\epsilon_0\epsilon_r)\mathbf{A} + \nabla \times (\mu_0^{-1}\mu_r^{-1}\nabla \times \mathbf{A}) - \sigma\nabla \times (\nabla \times \mathbf{A}) = (\sigma V_{\text{loop}}/2nr + J_{\phi}^e)\mathbf{e}_{\phi}, \mathbf{A} = A_{\phi}\mathbf{e}_{\phi}$$

Subdomains: 1, 2, 3, 4

Electric material properties and current sources

Library material: [dropdown] [Load...]

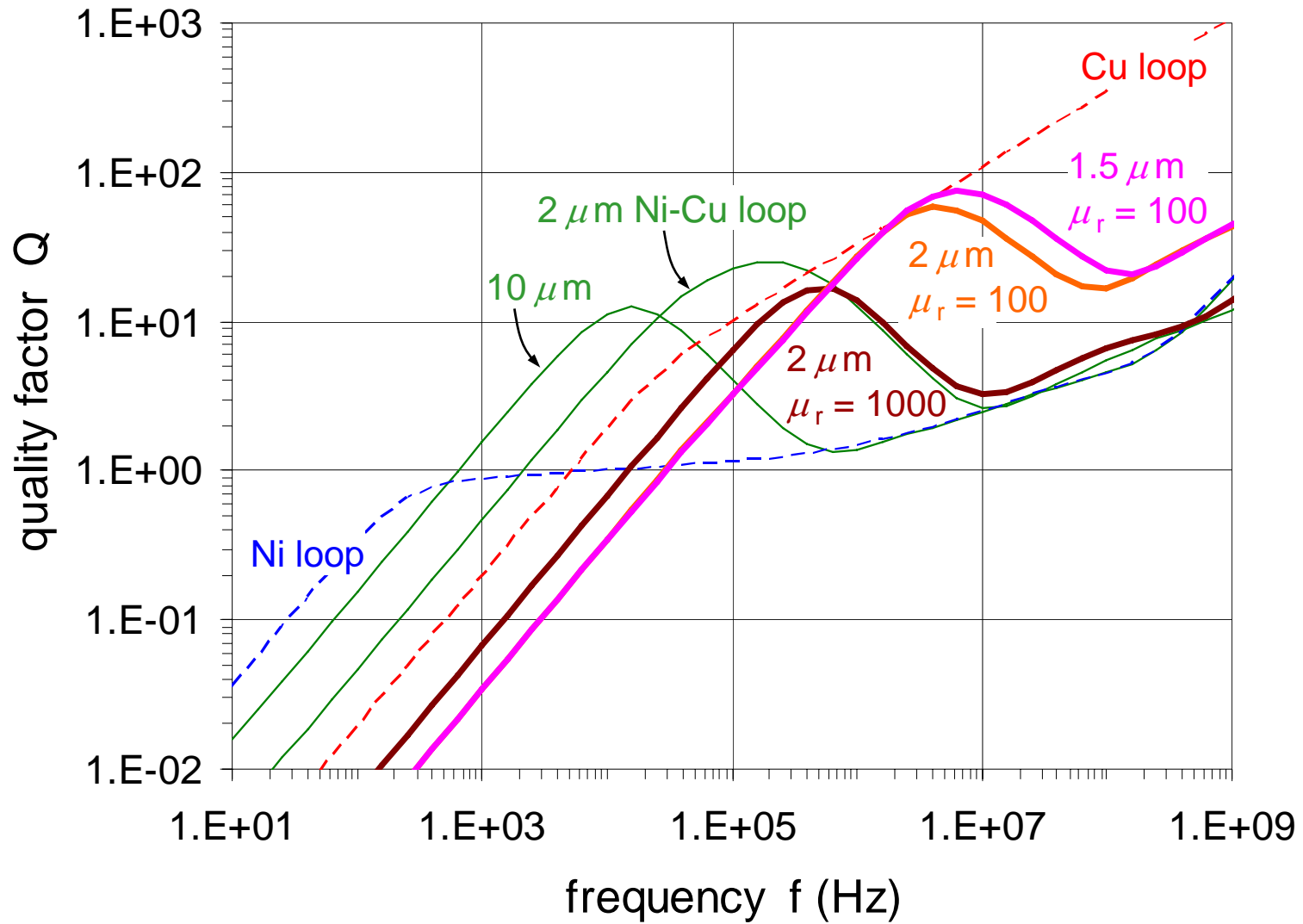
Constitutive relation

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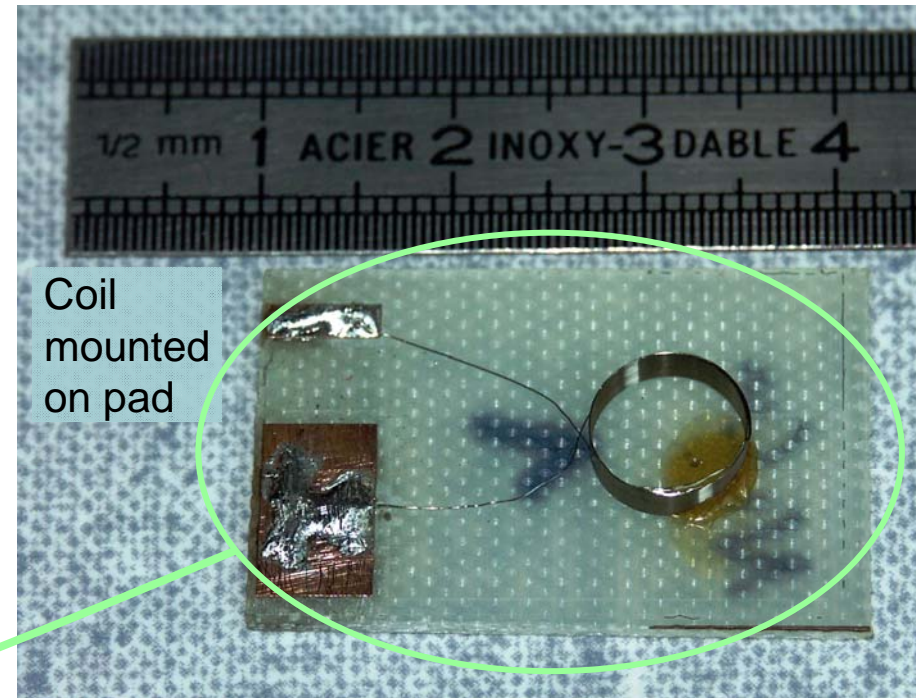
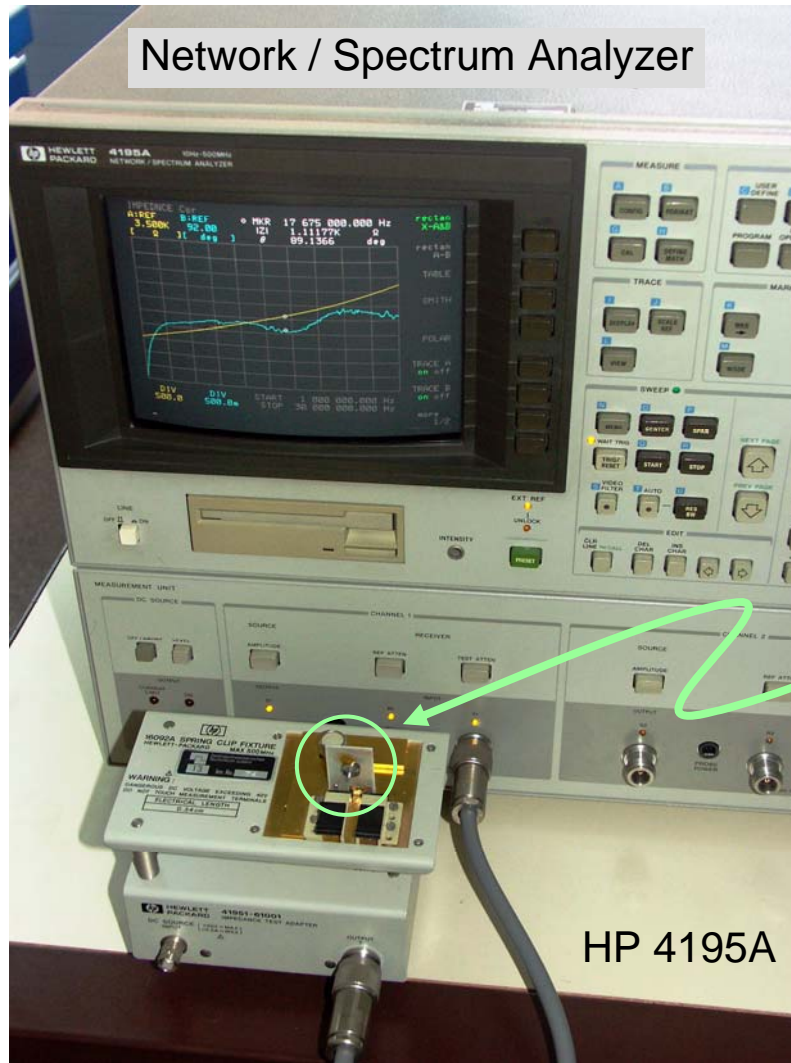
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J_{ϕ}^e	0	A/m ²	External current density
σ	sigma3	S/m	Electric conductivity
ϵ_r	1		Relative permittivity

Name	Expression	Value
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sigma3	1.0e7[S/m]	1e7[S/m]
sigma4	6.0e7[S/m]	6e7[S/m]
D	0.008	0.008
d	0.0012	0.0012
mur3	1000	1000
mur4	1	1

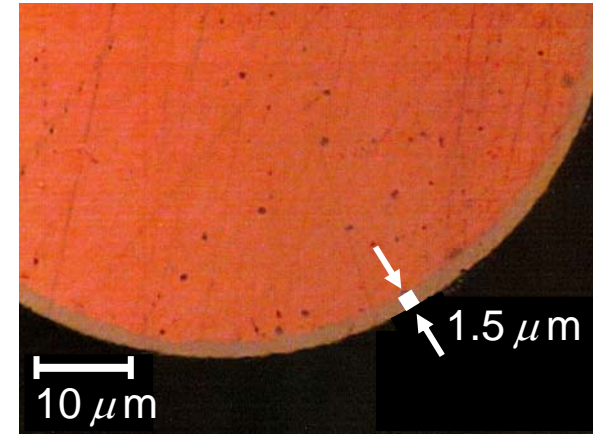
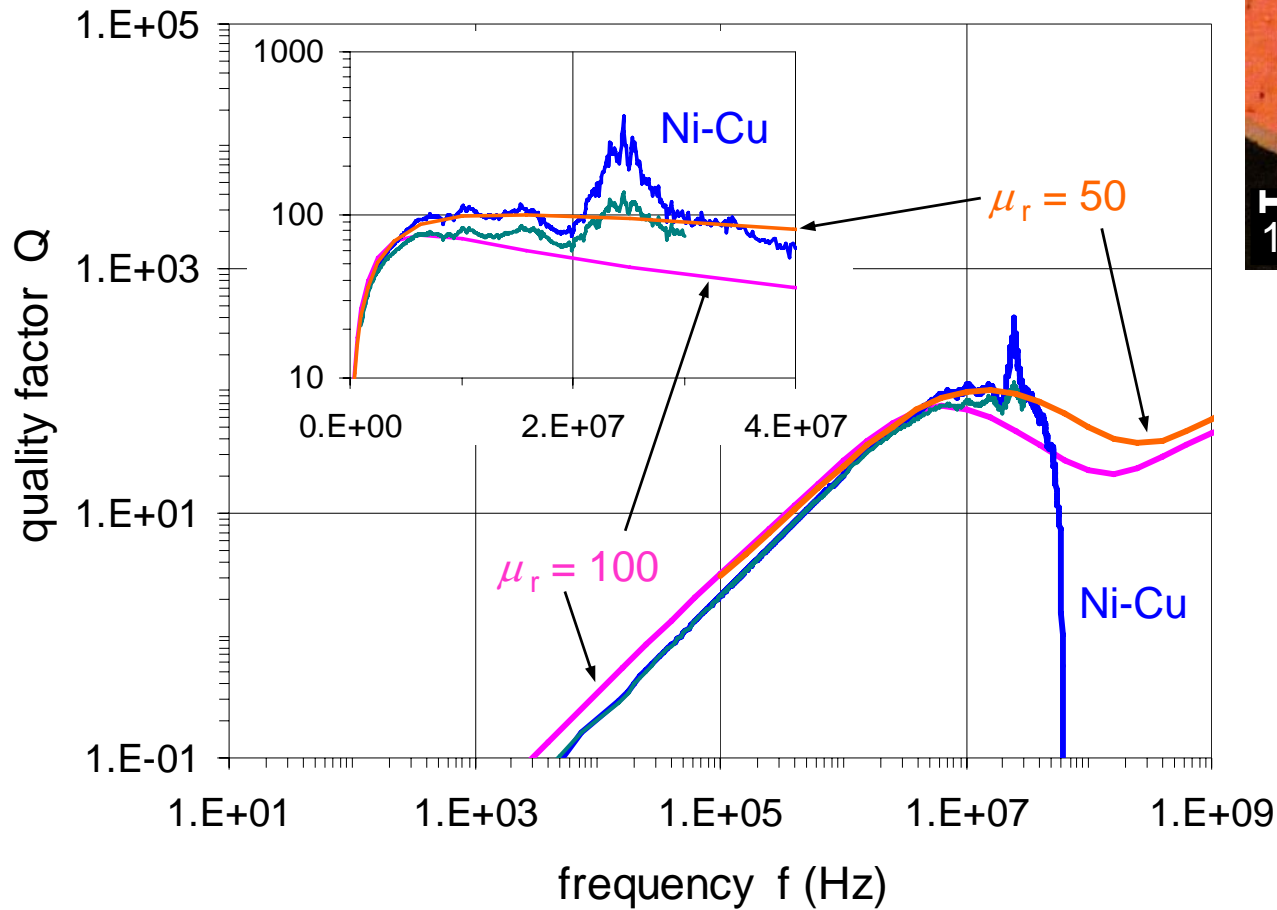
Q of Plated Coil



Measurement



Simul. vs. Experiment



Summary

- 1.** R, L and Q of plated loops and coils can be simulated with the classical electrodynamics AC/DC module of COMSOL
- 2.** For each plating thickness there exists a regime where Q is much larger than for pure copper or pure nickel loops and coils
- 3.** A true application of this phenomenon is not yet found, if not for the power transfer by magnetic resonance (Science, 317, p83, 2007)
- 4.** Excellent agreement between simulation and experiment can be found at modest frequencies below 10 MHz
- 5.** Comparison between simulation and experiment at higher frequency is not possible due to a stray capacitance and the occurrence of a resonance